

Abstract

Method for depositing an epitaxial layer on a front side of a wafer and device for carrying out the method

Device for depositing an epitaxial layer on a front side of a wafer having an orientation
5 notch, comprising a mechanism for holding and rotating a susceptor having a
susceptor support shaft and susceptor support arms; and ring which is held by the
susceptor support arms and has inwardly pointing projections; and the susceptor,
comprising a susceptor ring having a resting face for resting the wafer in the edge
region of a back side of the wafer and a stepped outer boundary of the susceptor ring
10 that is adjacent to the resting face, the resting face having an inwardly pointing
projection.

Drawing for the abstract: Fig. 10